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In re Application of: Choi, et al.

Serial No. 09/698,31/7

Filed: October 21, 2000

For: HIGH-PRECISION ORIENTATION

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I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on the date below:

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents Washington, D.C. 20231

Sir:

It is respectfully requested that this Information Disclosure Statement be entered and the documents listed on attached Form PTO-1449 (references A1-A118) be considered by the Examiner and made of record. A copy of each listed document is enclosed for the convenience of the Examiner.

Applicant also requests that the Examiner consider the following U.S. Patent applications with amendments, as noted: 09/908,455 (with amendment); 09/907,512 (with amendment); 09/920,341 (with amendment); 09/934,248 (with amendment); 09/976,681; and 09/908,765. Copies of these applications and amendments are enclosed for the convenience of the Examiner.

Should any fees be required, the Commissioner is authorized to charge said fees to Conley, Rose & Tayon, P.C. Deposit Account No. 50-1505/5119-08601.

Respectfully submitted,

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Date:

Form PTO-1449 (modified)

List of Patents and Publication For Applicant's Information
Disclosure Statement

(Use several sheets if necessary)

ATTY. DKT. NO. 5119-08601

SERIAL NO. 09/698,317

APPLICANT: Choi et al.

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